

Sources

离子源 >>

星弧涂层依据多年在PVD领域的设计和工艺经验，为客户提供应用于各行各业的各种离子源模块，其中包括：磁控溅射源，增强型磁控阴极弧源，阳极层离子束源以及过滤型阴极弧源。配备星弧的相应电源或其它品牌电源，这些离子源在应用于相关行业的真空系统中有杰出的性能表现。

With years of experience in PVD system design and thin film process, StarArc is able to provide various ion sources for wide range of industry. Our products cover sources of magnetron sputtering, magnetic enhanced cathodic arc, anode layered ion beam source and even filtered cathodic arc.

磁控溅射离子源-Magnetron sputtering source

- 应用于大规模量产的矩形靶设计，圆柱形多跑道设计和圆形平面靶设计。
- 高达50%的靶材利用率
- 配备星弧电源：DC，RF和中频AC
- Rectangular plenary design, circular design and multi-track cylindrical tube design for mass production
- Up to 50% target material utilization rate
- Equipped with DC, RF and medium frequency AC power supply

增强型磁控阴极弧源-Magnetic enhanced cathodic arc source

- 近100%的靶材离子化率
- 高达40%的靶材利用率
- 平面靶设计，中空水冷管状靶设计
- 有效的硬质涂层工艺离子源
- Near 100% target material ionization rate
- Up to 40% target material utilization rate
- Plenary target design, cylindrical water cooled tube target design
- Effective ion source for hard coating

过滤型磁控阴极弧源-Filtered cathodic arc source

- 有效过滤离子束中的有害颗粒
- 提供ta-C涂层
- 配合有效的电源和控制系统
- Effectively particle removing from beam
- Provide ta-C film
- Equipped with power supply and control system

阳极层离子束源-Anode layered ion beam source

- 离子能量高达2000eV
- 增强的离子束中和能力
- 配合以星弧直流EQ系列电源
- 应用于离子束清洗、刻蚀、辅助溅射等领域
- Up to 2000eV ion energy
- Enhanced neutralization of ion beam
- Equipped with StarArc's EQ series DC power supply
- Applied in ion beam cleaning, etching and ion beam assistant sputtering

